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Rabala

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application Serial No. 09/652,550
Filing Date August 31, 2000
Inventor Keiji Jono et al.
Assignee KMT Semiconductor, LTD
Group Art Unit 2811
Examiner Quang D. Vu
Attorney's Docket No. KM1-001
Title: Methods of Forming an Isolation Trench in a Semiconductor, Methods of
Forming an Isolation Trench in a Surface of a Silicon Wafer, Methods of
Forming an Isolation Trench-Isolated Transistor, Trench-Isolated Transistor,
Trench Isolation Structures Formed in a Semiconductor, Memory Cells and
DRAMs

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT


References -See Attached Form PTO-1449

The Examiner's attention is directed to the references which are listed on
the attached Form PTO-1449, copies of which are attached. No admission is
made regarding whether all the submitted references are prior art.

Citation of the referenced art is respectfully requested.

Respectfully submitted,

Dated: 3-10-03

By: 
D. Brent Kenady
Reg. No. 40,045

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Form PTO 1449 U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. KM1-001		SERIAL NO. 09/652,550	
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT: Keiji Jono et al.	
FILING DATE August 31, 2000				GROUP 2811	

U.S. PATENT DOCUMENTS							
*Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
	AA	6,034,409	03/07/2000	Sakai et al.			
	AB	6,171,924 B1	01/09/2001	Wang et al.			
	AC	6,154,417	11/28/2000	Kim			
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						

FOREIGN PATENT DOCUMENTS								
Document Number	Date	Country	Class	Subclass	Translation			
					Yes	No		
AL								
AM								
AN								
AO								
AP								

OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)			
AR			
AS			
AT			

EXAMINER	DATE CONSIDERED
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*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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